

|                                   |                                       |   |             |
|-----------------------------------|---------------------------------------|---|-------------|
| <b>Notice of References Cited</b> | Application/Control No.<br>10/759,108 | Applicant(s)/Patent Under<br>Reexamination<br>SCHWARM, ALEXANDER T. |             |
|                                   | Examiner<br>Ryan A. Jarrett           | Art Unit<br>2125  | Page 1 of 1 |

**U.S. PATENT DOCUMENTS**

| * |   | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Name | Classification |
|---|---|--|-----------------|------|----------------|
|   | A | US-  |                 |      |                |
|   | B | US-  |                 |      |                |
|   | C | US-  |                 |      |                |
|   | D | US-  |                 |      |                |
|   | E | US-  |                 |      |                |
|   | F | US-  |                 |      |                |
|   | G | US-  |                 |      |                |
|   | H | US-  |                 |      |                |
|   | I | US-  |                 |      |                |
|   | J | US-  |                 |      |                |
|   | K | US-  |                 |      |                |
|   | L | US-  |                 |      |                |
|   | M | US-  |                 |      |                |

**FOREIGN PATENT DOCUMENTS**

| * |   | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Country | Name | Classification |
|---|---|--|-----------------|---------|------|----------------|
|   | N |  |                 |         |      |                |
|   | O |  |                 |         |      |                |
|   | P |  |                 |         |      |                |
|   | Q |  |                 |         |      |                |
|   | R |  |                 |         |      |                |
|   | S |  |                 |         |      |                |
|   | T |  |                 |         |      |                |

**NON-PATENT DOCUMENTS**

| * |   | Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)   |
|---|---|---|
|   | U | Tan, L., Cameron, D., and C. McCorkell. "Steady-State Regression Analysis and Optimization of Multivariable Plasma Etching System". IEEE (1994): 1986-1991. |
|   | V |   |
|   | W |   |
|   | X |   |

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.